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# Ultra-high photon flux high-harmonic generation

Maxim Tschernajew<sup>1</sup>, Steffen Hädrich<sup>1</sup>, Robert Klas<sup>2,3</sup>, Martin Gebhardt<sup>2,3</sup>, Roland Horsten<sup>4</sup>,  
Sven Weerdenburg<sup>4</sup>, Sergey Pyatchenkov<sup>4</sup>, Wim Coene<sup>4,5</sup>, Sven Breikopf<sup>1</sup>, Oliver Herrfurth<sup>1</sup>,  
Jan Rothhardt<sup>2,3</sup>, Tino Eidam<sup>1</sup> and Jens Limpert<sup>1,2,3,6</sup>

1. Active Fiber Systems GmbH, Ernst-Ruska-Ring 17, 07745 Jena, Germany

2. Institute of Applied Physics, Abbe Center of Photonics, Friedrich-Schiller-Universität Jena, Albert-Einstein-Str. 15, 07745 Jena, Germany

3. Helmholtz-Institute Jena, Fröbelstieg 3, 07743 Jena, Germany

4. Optics Research Group, Delft University of Technology, 2628 CH, Delft, The Netherlands

5. ASML Netherlands B.V., P.O. Box 324, 5500 AH Veldhoven, The Netherlands

6. Fraunhofer Institute for Applied Optics and Precision Engineering, Albert-Einstein-Str. 7, 07745 Jena, Germany

Author e-mail address: publications@afs-jena.de

**Abstract:** We present a highly stable, easy-to-use HHG source delivering a record photon flux of  $>10^{11}$  photons/s at 69eV-75eV, being tunable to approx. 100eV which will be used for future photon-hungry applications. © 2022 The Author(s)

High-harmonic generation (HHG) driven by ultrashort laser pulses is an established process for the generation of coherent extreme ultraviolet (XUV) to soft X-ray radiation, which has found widespread use in various applications [1]. In recent years photon-hungry applications such as coherent diffractive imaging [2,3] and applications based on statistical analysis [3] have required more powerful HHG sources employing higher repetition rates. This need can be addressed by using high-average-power fiber lasers as the HHG drivers [4]. Here, we present a HHG-based XUV source providing a large photon flux across a wide range between 66 eV and 150 eV. It is driven by a commercial XUV beamline from Active Fiber Systems GmbH consisting of an 100-W average power fiber-laser system delivering up to 300  $\mu$ J at <300-fs pulse duration. For HHG, this system is operated at 100 W and 600 kHz. A post-compression unit is part of the device to shorten the pulses to  $\sim$ 35 fs, the average power remains at 63W. The turnkey source provides unprecedented photon flux of  $>10^{11}$  photons/s in each harmonic between 69 eV and 75 eV (HH57-HH63). All flux values are given at the generation point, i.e. directly after the source.

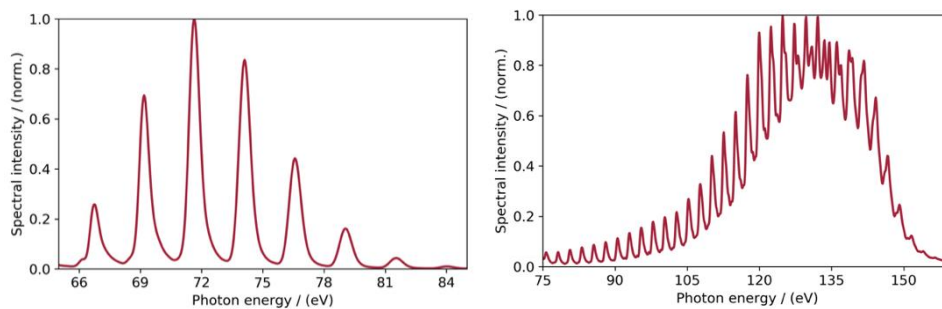


Fig. 1 Left: HHG spectrum generated in argon and optimized for  $\sim$ 70eV operation. Right: HHG spectrum generated in neon and optimized for operation at  $>92$ eV.

Figure 1 (left) shows a typically measured HHG spectrum using argon. The photon flux is analyzed by accounting for the transmission of the measurement apparatus (flat-field grazing incidence spectrometer) showing that the strongest harmonic (HH59) at 71 eV features  $3 \cdot 10^{11}$  photons/s. This constitutes a record-high photon flux at this photon energy for any reported laser-driven source to date [5,6,7]. Therefore, it can be expected that this source will enhance and speed up applications that currently suffer from long measurement times. A second focus of optimization is put on the spectral range around 93 eV (Fig.1 (right)), because of its significance for semiconductor industries [8]. Without changing the optical setup, the source can be tuned to this wavelength by using neon. At 93 eV, the source delivers  $5 \cdot 10^9$  photons/s/(1% bandwidth), which enables numerous experiments in that important wavelength range. Generally, the source can deliver photon energies of up to 150 eV with a photon flux  $>10^{10}$  photons/s/(1% bandwidth) for harmonics between 115eV and 140eV, which also constitutes a record flux in that spectral range. Generally, an important aspect of each HHG source regardless of its particular application is their user-friendliness and output stability. Over the time span of one hour, the photon flux is as stable as  $\sim$ 1% RMS in the spectral range around 70 eV and 90 eV, respectively.

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